

In the Specification

At page 1, before the TECHNICAL FIELD, insert:

**CROSS REFERENCE TO RELATED APPLICATION**

This patent application is a Divisional Application of U.S. Patent Application Serial No. 09/026,042, filed February 19, 1998, entitled "RF Powered Plasma Enhanced Chemical Vapor Deposition Reactor and Methods of Effecting Plasma Enhanced Chemical Vapor Deposition," naming Sujit Sharan, Gurtej S. Sandhu, Paul Smith and Mei Chang as inventors, the disclosure of which is incorporated by reference. This application is related to U.S. Patent No. 6,159,867, filed August 19, 1999, which is a divisional application of U.S. Patent No. 6,112,697, filed February 19, 1998.

Replace the paragraph beginning on page 11, line 1 to page 12, line 4,  
with:

*R  
P*

In accordance with a preferred aspect of the invention, RF power splitter 36 comprises a center tapped transformer in which the output power provided to the respective first and second electrodes is substantially equal in magnitude. Such is desirable when power splitter 36 is used in connection with the PECVD reactor of Fig. 2. In such circumstances, it has been found that the ratio of power which is applied to the electrodes is related to surface areas 24, 28 of electrodes 22, 26. Hence, by changing or manipulating the subject surface areas, one can manipulate or select the power ratio and affect the magnitudes of the first and second power components which are "seen" by the respective electrodes to which such power components are applied. In the illustrated and preferred embodiment, such surface areas are different from one another, with the susceptor surface area being larger than the shower head surface area. Such enables a power differential to be developed according to a definable relationship. Such relationship consists of a predefined relative magnitude which is directly proportional to the inverse ratio of the 4th power of the areas of the electrodes. Put another way, by varying the relative surface area ratios as between the susceptor and shower head, a variation in power applied thereto can be effectuated. In the illustrated and preferred embodiment, second electrode or shower head 26 has a surface area which is less than or smaller than the surface area of the first electrode or susceptor 22. Such results in a higher magnitude of power

A.  
B.  
conclusion

being applied to the shower head than is applied to the susceptor. This advantageously allows deposition of reactants introduced into chamber 21 in a preferred manner by causing highly energetic species to be drawn toward and in the direction of the electrode supporting the workpiece.

### In the Claims

Please cancel claims 1-41 without prejudice and add new claims 42-62 as follows:

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